

A B S T R A C T

PHOTOMASK BLANK AND METHOD FOR MANUFACTURING PHOTOMASK

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According to one embodiment, a photomask blank wherein
a second film (14) is stacked on a first film (13), the
first film containing chromium and which is not
substantially etched by the dry etching using fluorine
10 and which is etchable by the dry etching using oxygen-
containing chlorine, and the second film containing no
chromium and which is etchable by dry etching using
fluorine and dry etching using oxygen-containing
chlorine.

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FIG. 1